

WAFER FILM FRAME CLEANER TRACK SYSTEM

Please contact Sales sales@picotrack.com for more information



Track System Specification	Description
System Designed	US Standard System
System Configuration	<div style="border: 1px solid black; border-radius: 15px; padding: 5px; display: inline-block;"> CLEANING SYSTEM - SST FRAME WAFER SIZE " 4", 6" & 8" </div>
System dimension	46.50" length x 30.50" width x 60" height
Wafer size	4" up to 8"
Wafer Film Frame shape	SST Wafer film frame round
Wafer material	Silicon
Wafer Handling	Manual loading/unloading
System Controller	PC & PLC Controller with Windows OS based
Chemical Cabinet	Canisters
Cleaner Chamber Catch cup set	SST
Spindle Chuck with holders	Aluminium anodize universal size (4" to 8")
Hand Safety sensor	Optical
System Drain	Diverter Valve Drain Unit for wasted liquid selection
System Exhaust	SST common manifold
CO2 fire suppression system	Optional
Film Frame Cleaner	1 Module
Spindle Unit	Up/down motion
SST Catch Cup Set	Fixed
Safety chamber cover	SST with transparent glass and air cylinder control (open/close)
Maximum spin speed	4000 rpm
Spin motor	High Torque Servo motor (brushless) & servo controller
Spin direction	Clockwise (+) or Counter Clockwise (-)
Spin speed accuracy	± 3 rpm
Acceleration range	20-30000 RPM/sec
Dispense arm accuracy	± 0.1 mm
Dispense arm motion control	Stepper motor and driver
Dispense method	Static, radial and sweep
Dispense arm # 1	Solvents stream or spray nozzles (by liquid high pressure pump and canister)
Dispense arm # 2	N2 air Jet nozzle blow off (up to 100 PSI)
Solvent liquids temperature control	Optional ≤ 1°C (10-50°C range)
Back side rinse D.I. Water or solvents	Yes
Back side rinse N2 air blow	Yes
N2 Air Filter	0.2µm
Solvents Filter	0.1µm